

Interference Search

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L10	442	((ammonia or NH3 or NH?sub\$3 or N-H or ((N2 or nitrogen or N?sub\$3) near5 (H2 or H?sub\$3 or hydrogen))) same (insulat\$6 or ILD or IMD or IDL or IML or TEOS or tetraethoxysilane or tetraorthosilicate or tetraorthosilane or tetraethoxysilane or dielectric or SiO2 or SiO?sub\$3) same plasma). clm.	US-PGPUB; USPAT	OR	ON	2006/02/15 15:40
L11	0	10 and ((dehydrat\$6 or (de adj hydrat\$6)) same (alcohol or IPA or isopropanol or isopropylalcohol)). clm.	US-PGPUB; USPAT	OR	ON	2006/02/15 15:43
L12	1	10 and (dehydrat\$6 or (de adj hydrat\$6)).clm.	US-PGPUB; USPAT	OR	ON	2006/02/15 15:43
L13	11	10 and (alcohol or IPA or isopropanol or isopropylalcohol). clm.	US-PGPUB; USPAT	OR	ON	2006/02/15 15:43
L14	11	12 or 13	US-PGPUB; USPAT	OR	ON	2006/02/15 15:43

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	21064	(ammonia or NH3 or NH?sub\$3 or N-H or ((N2 or nitrogen or N?sub\$3) near5 (H2 or H?sub\$3 or hydrogen))) same plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/15 13:28
L2	35844	(ammonia or NH3 or NH?sub\$3 or N-H or ((N2 or nitrogen or N?sub\$3) near5 (H2 or H?sub\$3 or hydrogen))) same (insulat\$6 or ILD or IMD or IDL or IML or TEOS or tetraethoxysilane or tetraorthosilicate or tetraorthosilane or tetraethoxysilane or dielectric or SiO2 or SiO?sub\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/15 13:29
L3	25671	(insulat\$6 or ILD or IMD or IDL or IML or TEOS or tetraethoxysilane or tetraorthosilicate or tetraorthosilane or tetraethoxysilane or dielectric or SiO2 or SiO?sub\$3) same (dehydrat\$6 or (de adj hydrat\$6) or alcohol or IPA or isopropanol or isopropylalcohol)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/15 13:32
L4	312	1 and 2 and 3 and (@ad<"20031029" or @rlad<"20031029")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/15 13:32
L7	297	4 and ((self adj orientat\$6) or Ti or titanium or Pt or platinum or silicon or Si or Cu or copper or aluminum or Ta or tantalum or Ir or iridium or Ta2O5 or (Ta?sub\$3 adj O?sub\$3) or IrO2 or IrO?sub\$3) same (ammonia or NH3 or NH?sub\$3 or N-H or ((N2 or nitrogen or N?sub\$3) near5 (H2 or H?sub\$3 or hydrogen))) or dehydrat\$6 or (de adj hydrat\$6) or alcohol or IPA or isopropanol or isopropylalcohol or insulat\$6 or ILD or IMD or IDL or IML or TEOS or tetraethoxysilane or tetraorthosilicate or tetraorthosilane or tetraethoxysilane or dielectric or SiO2 or SiO?sub\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/15 13:40

L8	238	7 and semiconductor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/15 13:41
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